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Development of Multilayer Spectral Purity Filters for EUVL Tools

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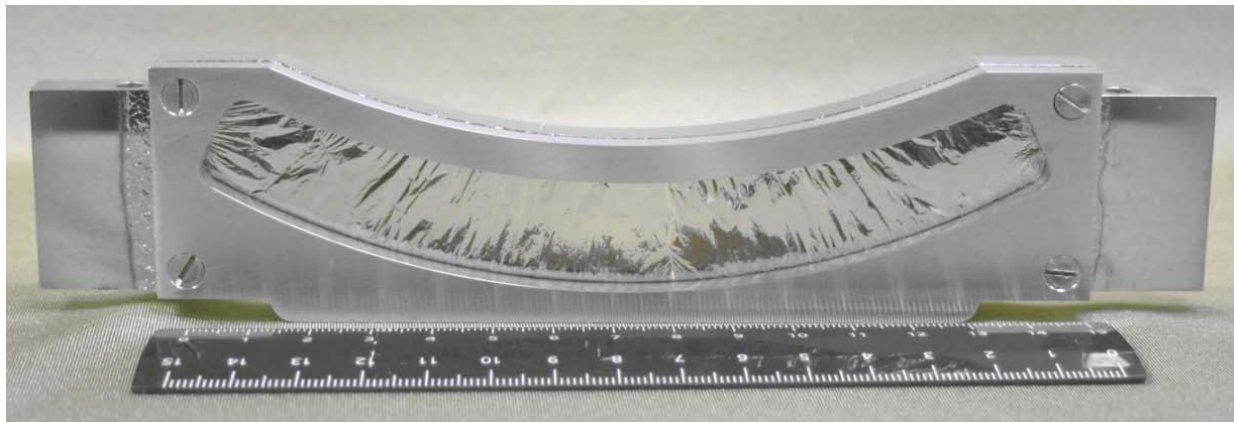
Agenda

- Previous results with structures containing Zr, Si, ZrSi₂
- Towards requirements for HVM tools
- Introducing Mo, MoSi₂ to retard oxidation effects
- Tests with high power density loads
- Results of high temperature exposures
- Estimation of tensile strength
- Fabrication of pilot samples with large clear aperture
- Conclusions, further tasks

Zr/Si multilayer structures (2004-2006)

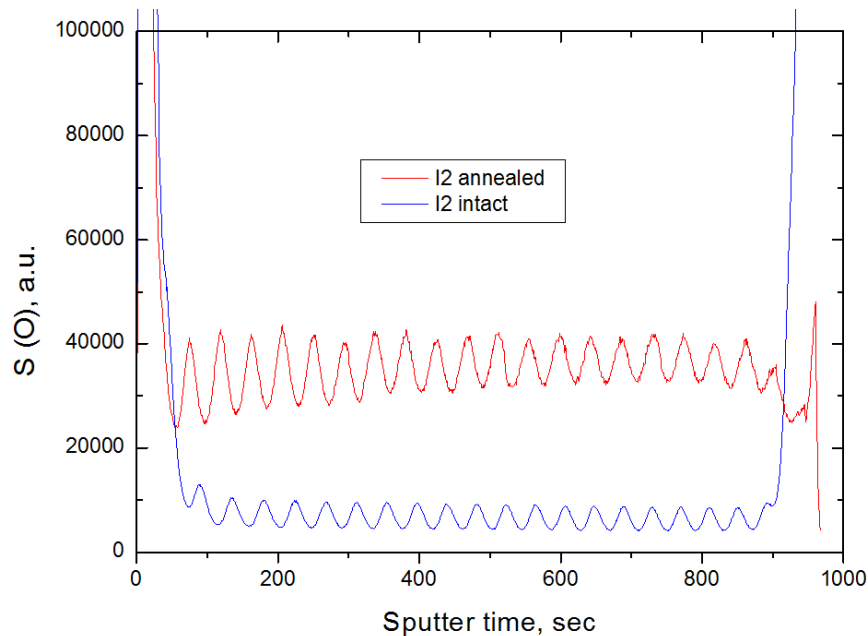
- Suppression of DUV at $<1.5 \text{ W/cm}^2$ absorbed
- 55 nm, $T_{IB} = 76\%$, $T_{DUV} = 0.2 \div 1\%$,
- $<600 \text{ }^\circ\text{C}$, T_{IB} drop 3-4% after few hours
- Large dimensions

SPF fabricated for Alpha Demo Tool (2006)



Zr/ZrSi₂ multilayer structures (2008)

- **Suppression of DUV and 10.6 μm at 3 W/cm² absorbed**
- **60 nm, $T_{\text{IB}} = 70\%$, $T_{\text{DUV}} = 0.2 \div 1\%$, $T_{10.6} = <2\%$, $R_{10.6} \rightarrow 80\%$**
- **$<700^\circ\text{C}$, T_{IB} drop 3-4% after 6-8 hours,**
associated with high-temperature oxidation



**Pre- and post-exposure
SIMS analysis revealed
accumulation of oxygen,
correlated with ZrSi₂
location**

Towards requirements for HVM tools

We must expect:

- **Further essential increase of irradiation power, leading to SPF temperatures above 1000 °C**
- **Required stability/lifetime – on a scale of months**

Major issues:

- **high-temperature oxidation**
- **mechanical stress and repetitive deformation**
caused by pulsed irradiation and power modulation

Introducing structures with Mo, MoSi₂ to retard oxidation effects

MoSi₂ cup | Mo-ZrSi₂ multilayer core | **MoSi₂ cup**

Ductile padding layers of ZrSi₂ enable
lifting process, resistance to deformations
and high IB transmission

Spectral data for a 53.5 nm sample:

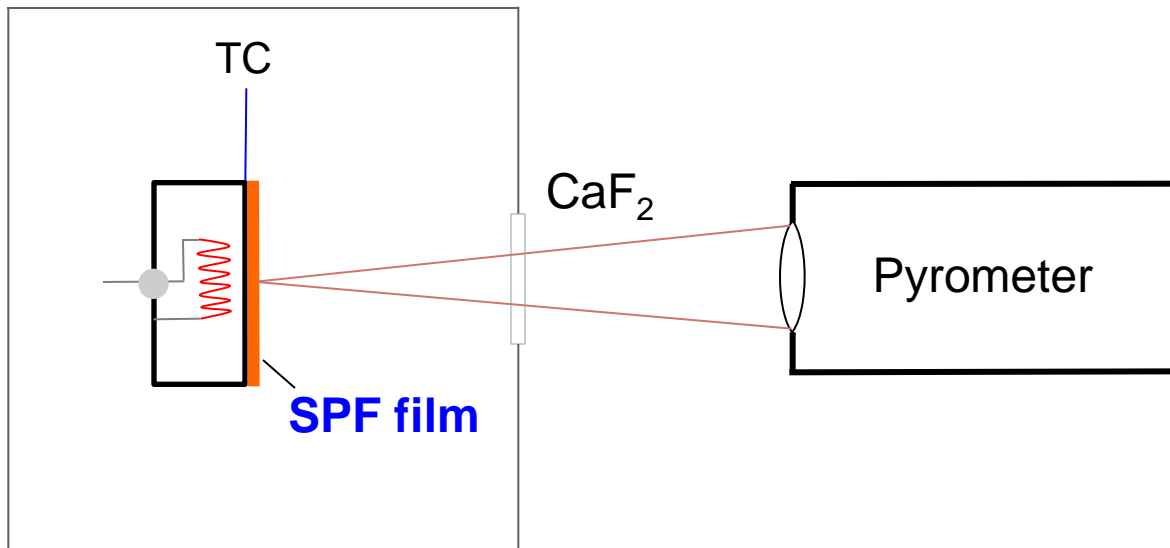
R _{10.6} , %	T _{10.6} , %	T ₆₃₃ , %	T _{13.5} , %
83.2	0.84	0.72	71.4

Tests with high power density loads

- Heating with CO₂ laser beam of samples at 10⁻⁷ mbar (H₂O)
- Power density: incoming <40 W/cm², absorbed <8 W/cm²
- Temperature range 700 ÷ 1100 °C (at central point)
- Exposure time 17-20 hours (to measure IB transmission drop)
- Power modulation by laser beam interruption at a few Hz
- Temperature recording by pyrometer, calibrated on thermocouple in full range
- Pre- and post-exposure transmission measurements (IB, DUV, 10.6 μm); reflectivity for 10.6 μm on supported films
- Pre- and post-exposure SIMS analysis

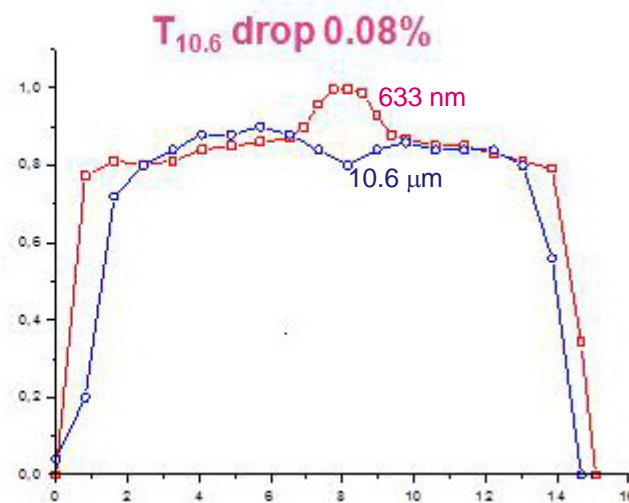
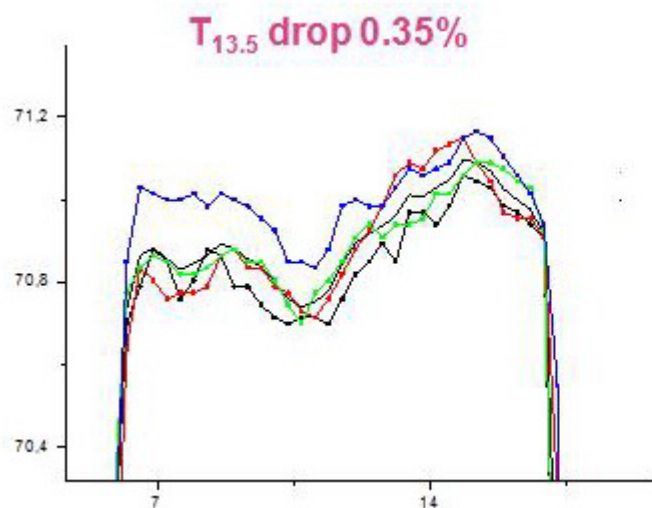
Pyrometer calibration

(determination of film emissivity)



Material emissivity value in pyrometer settings adjusted to get reading coinciding with that of the thermocouple

Results of high temperature exposures



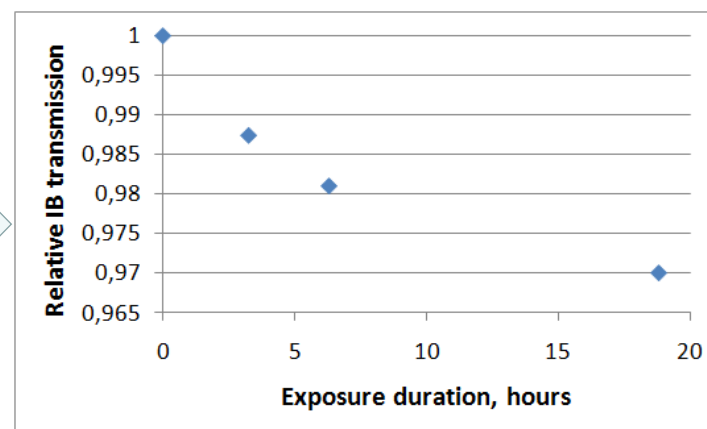
Exposure facts:

900 °C (4.3 W/cm²)

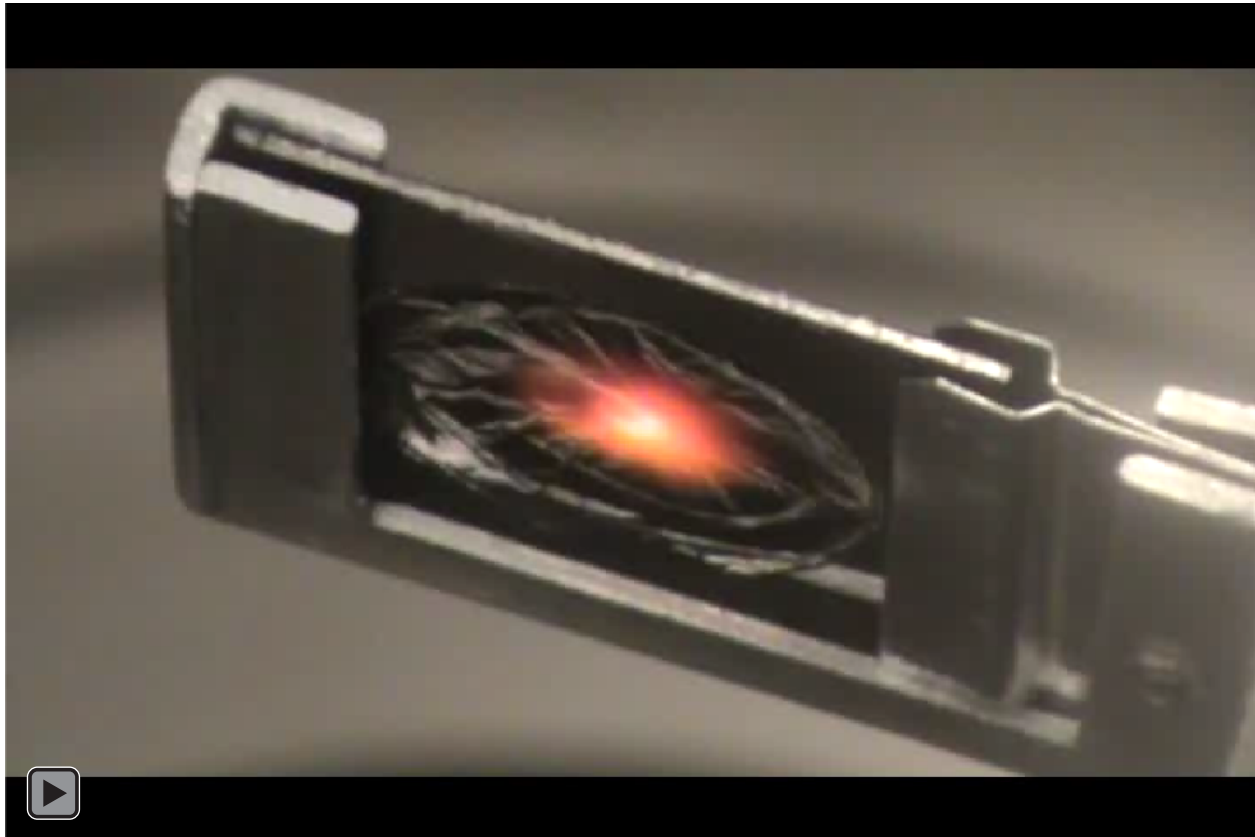
0,35% drop of
IB transmission
after 17 hours

950-970 °C (5 W/cm²)

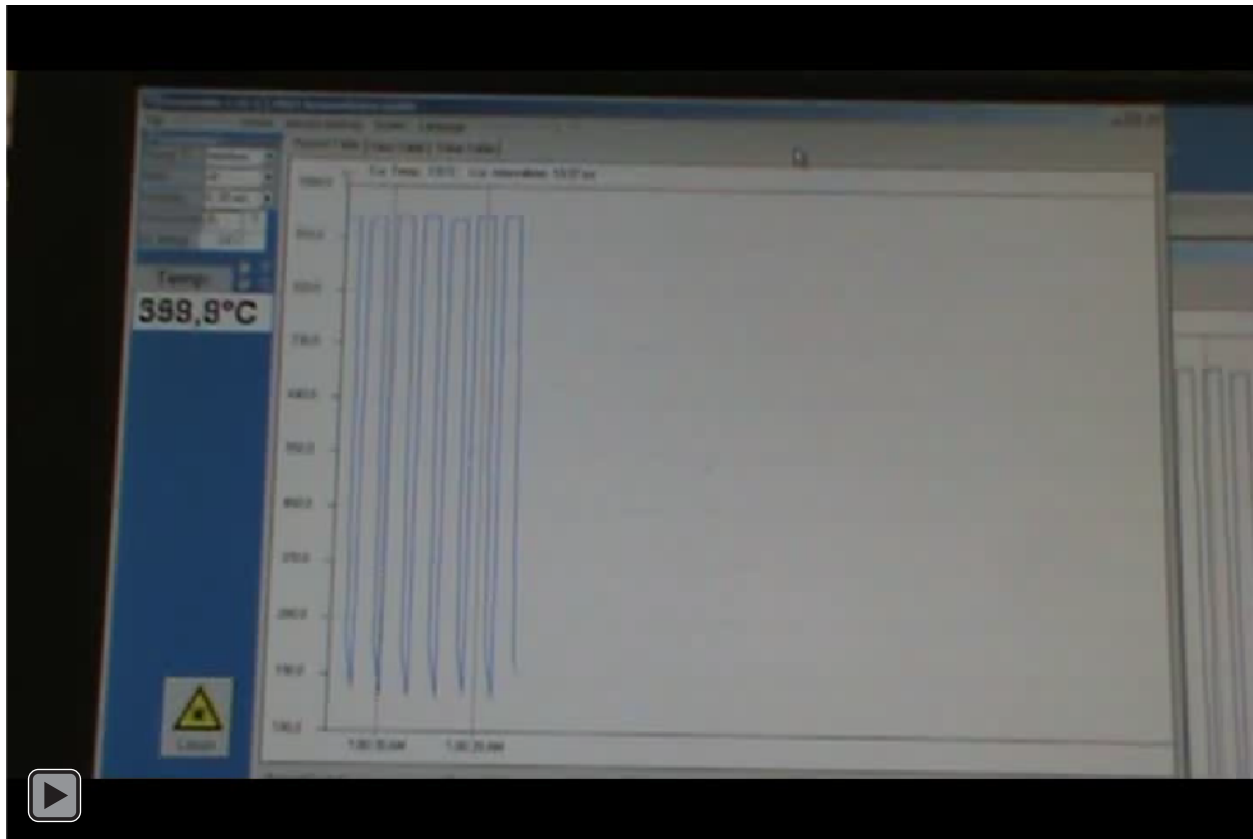
2% drop of
IB transmission
after 19 hours



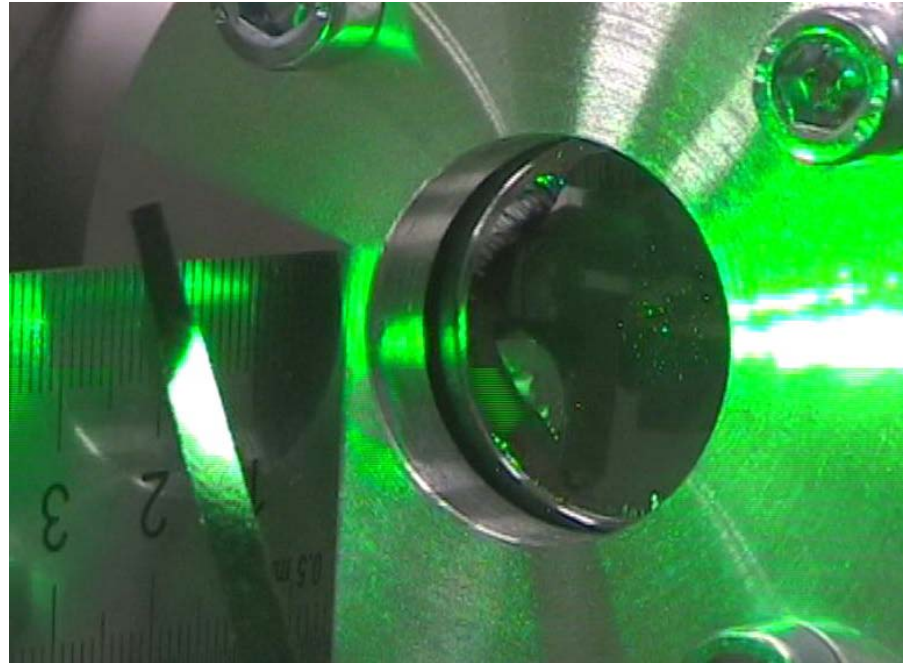
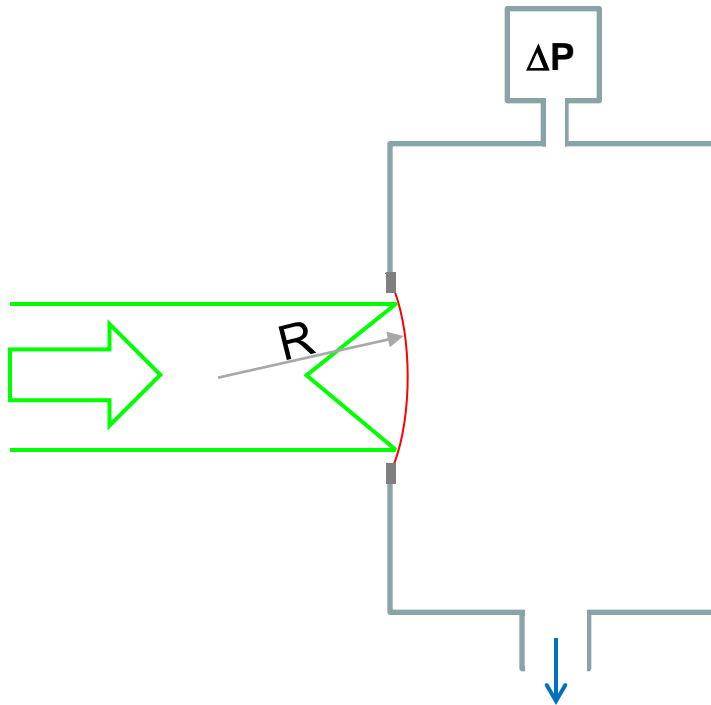
Modulated irradiation of SPF sample



Recorded temperature variation



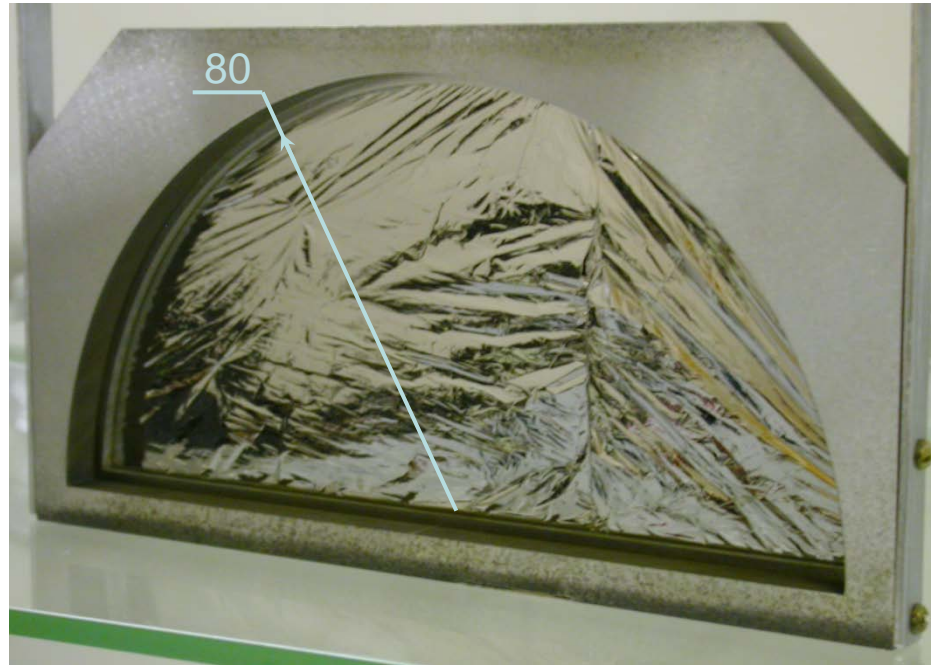
Estimation of film tensile strength from pressure differential and curvature



$$\sigma = \Delta P \times R / 2h \quad \Rightarrow \quad 1 \div 2 \text{ GPa}$$

SPFs with large clear apertures

Pilot 90 nm SPF film on technological frame



Apertures above 200 mm are feasible

Conclusion

- Recent progress in SPF parameters, in particular anti-oxidation features, is not sufficient for expected HVM conditions

Priority tasks

- Search for padding layers with ultimate chemical and mechanical characteristics
- Providing experimental possibilities for scalable tests of SPF samples under intensified oxidation and mechanical load

Acknowledgment

To V. Banine, A. Yakunin – for constant stimulating interest and detailed discussions of HVM related SPF issues